

EE143 Lab Week 6 Measurement Checklist

1) Lithography

Time (sec)		
Softbake:		
Exposure:		
Developer:		
Hardbake:		
Linewidth (um) of Photoresist		
Nominal	Measured	% Overetch
2	
3		
4	
8		..

Take a photo of the linewidth marks

Vernier Misalignment:	
X	
Y	

Take 3 Photos: Overall Vernier Pattern, and zoomed photo of X & Y vernier patterns

2) Contact Cut

Contact Etch Time:		
Linewidth (um) of Contact after etch		
Nominal	Measured	% Overetch
2	
3		
4		..
8		

Questions:

Calculate % overetch of the linewidth patterns

What was a visual method for determining completion of etching?